



PTO/SB/08A (10-01)

Approved for use through 10/31/2002.OMB 0651-0031

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Substitute for form 1449A/PTO  <b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  (use as many sheets as necessary)				<b>Complete if Known</b>	
				Application Number	09/988,984
				Filing Date	November 19, 2001
				First Named Inventor	John T. Moore
				Art Unit	2812 2823
				Examiner Name	Not Yet Assigned T. PHAM
Sheet	1	of	4	Attorney Docket Number	M4065.0608/P608

U.S. PATENT DOCUMENTS					
Examiner Initials*	Cite No. <sup>1</sup>	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number-Kind Code <sup>2</sup> (if known)			
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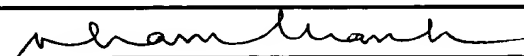
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TWP	BA	JP 56126916	10/1981	Akira et al.		
	BB					

Examiner Signature		Date Considered	7/21/03
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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant

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		Art Unit	2842 2823		
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Sheet	4	of	4	Attorney Docket Number	M4065.0608/P608

OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS			
Examiner Initials	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>2</sup>
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